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Wei-Tsu has more than 50 patents to his credits. He has published 110+ technical papers and various book chapters covering all different technical aspects of CMP, post-CMP cleaning, low-k dielectrics, Cu plating and interconnects, and am often invited to give technical presentations worldwide at major integrated circuit (IC) device processing related international conferences. Recently, he was appointed as guest editor for Nanomaterials special issue on "Innovation in Nanoelectronic Semiconductor Devices and Materials.

Wei-Tsu received his Ph.D. from the University of Texas at Austin in Materials Science and Engineering, and B.S. degree in Metallurgy and Material Science from National Cheng Kung University in Taiwan.